

APPENDIX A

IN THE ABSTRACT:

Please replace the Abstract with the following new Abstract.

[A scan type exposure apparatus includes a first movable stage on which a first object is to be placed, a second movable stage on which a second object is to be placed, a projection optical system for projecting a pattern of the first object onto the second object, and a scanning mechanism for scanningly move the first and second movable stages in a timed relation with each other, relative to the projection optical system, while the pattern of the first object is projected by the projection optical system onto the second object, wherein data, corresponding to a change in exposure condition as measured beforehand and to be produced by moving at least one of the first and second movable stages, is stored and wherein scan exposure is performed while reflecting a correction value, as determined on the basis of the data stored to the drive of at least one of the first and second movable stages.]

-- A scan type exposure apparatus includes a scanning mechanism and a signal system.
The signal system is arranged to scanningly move first and second stages in a timed relation with each other, relative to a projection optical system, while a pattern of a first object is projected onto a second object. The signal system is systemized to store data
is produced in response to scan motion of at least one of the first and second stages and in

accordance with one of scan acceleration and scan speed. The data is measured beforehand by obtaining data of a projected image of the pattern of the first object, being formed on the second object through the projection optical system, while scanningly moving at least one of the first and second stages. The signal system is further systemized to control a drive of the first and second stages in an actual exposure process while reflecting a correction value, as determined on the basis of the data stored, to the driving of at least one of the first and second stages. --